Fig. 1A formation of base insulating film/ formation of semiconductor film



Fig. 1B laser anneal

Fig. 1C heat treatment process

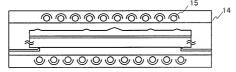


Fig. 1D formation of semiconductor film



Fig. 2A formation of base insulating film/ formation of semiconductor film

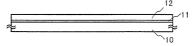


Fig. 2B laser anneal

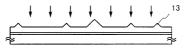


Fig. 2C formation of semiconductor film

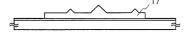


Fig. 2D heat treatment process



Fig. 3A formation of base insulating film/ formation of semiconductor film

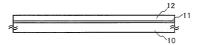


Fig. 3B irradiation of strong light

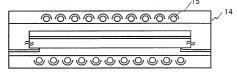


Fig. 3C laser anneal

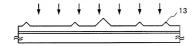


Fig. 3D heat treatment process



Fig. 3E formation of semiconductor film



Fig. 4A formation of conductive film/formation of insulating film /formation of semiconductor film

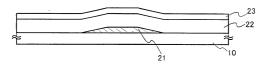


Fig. 4B laser anneal

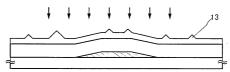


Fig. 4C heat treatment process

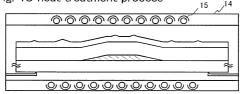
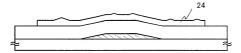
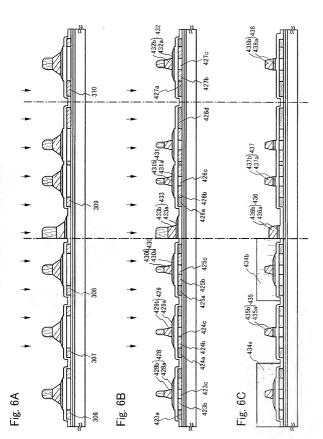


Fig. 4D formation of semiconductor film





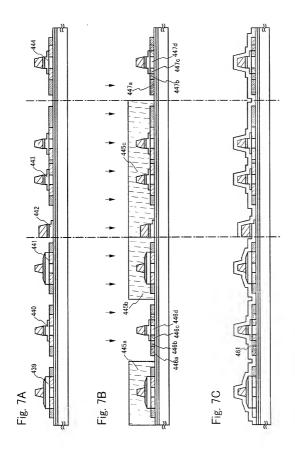


Fig. 8

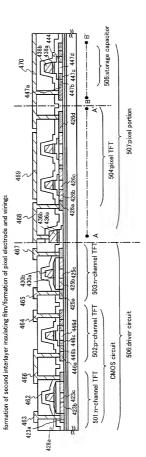


Fig. 9

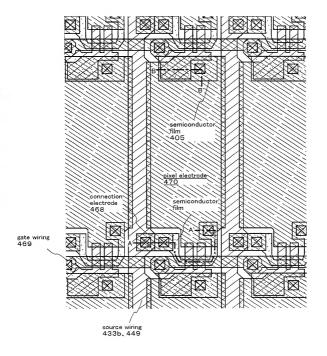


Fig. 10

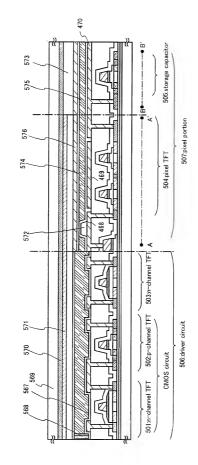


Fig. 11

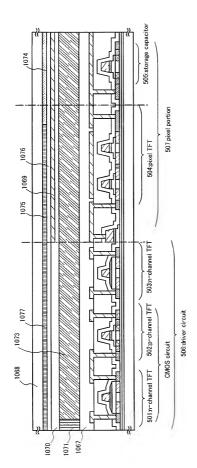


Fig. 12

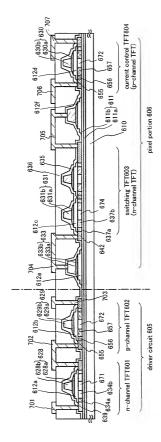
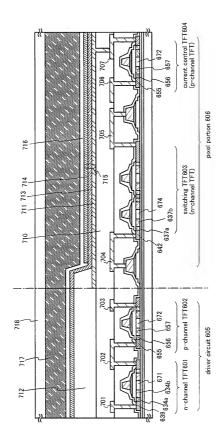


Fig. 13



pixel portion 806

Fig. 15

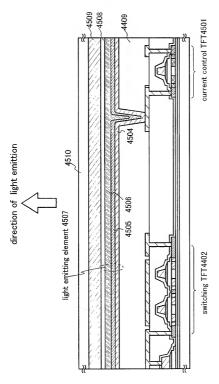
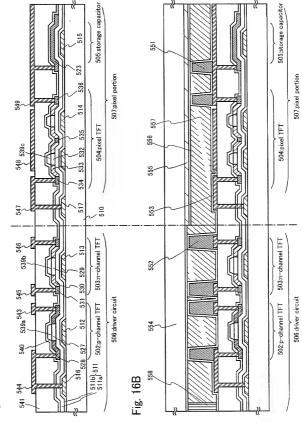
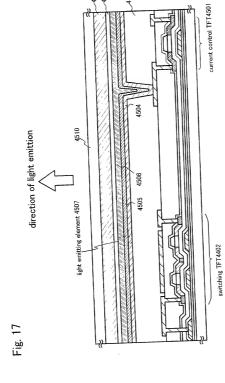
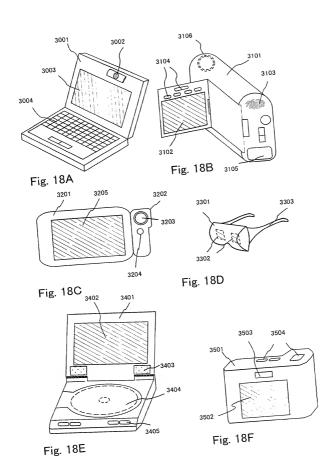


Fig. 16A







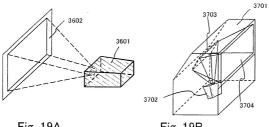


Fig. 19A

Fig. 19B

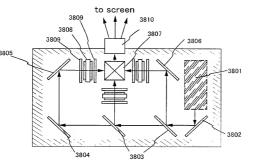


Fig. 19C

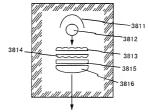


Fig. 19D

